

09/822191

(b) Amendment to the Claims

Please cancel claims 6, 8, 12-14, 20, 22 and 26-30 without prejudice or disclaimer of subject matter.

Kindly amend claims 1, 10, 11, 15, 24 and 25 as follows. A detailed listing of all the claims is provided.

1. (Currently Amended) An exhaust processing method of exhausting a processing space for subjecting a substrate or a film to plasma processing with plasma, which comprises:
  - (a) providing a chemical-reaction inducing unitmeans having a heating element comprising a first metal member in an exhaust line, said exhaust line connecting the processing space and an exhaust unitmeans for exhausting the processing space, wherein the first metal member is connected to a power source;
  - (b) providing a plasma blocking unitmeans consisting of a second metal member electrically grounded between the processing space and the first metal member; wherein the chemical-reaction inducing unit is provided at a position where the plasma reaches and the plasma blocking unit blocks the plasma from reaching the chemical-reaction inducing unit; and
  - (c) causing chemical reaction of at least either an unreacted gas or a by-product exhausted from the processing space via heat from said heating element while blocking plasma in the processing space from reaching the chemical-reaction inducing means via said plasma blocking means-unit acts to reduce electron number density in the plasma reaching the chemical-reaction inducing unit by at least 90%.